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(54) Title: A FLUOROMETRIC METHOD FOR INCREASING THE EFFICIENCY OF THE RINSING AND WATER RECOVERY PROCESS IN THE MANUFACTURE OF SEMICONDUCTOR CHIPS

(57) Abstract

A method for determining wafer cleanliness by fluorometric monitoring of the impurities in the semiconductor wafer chip rinse solution. A clean chip is indicated by a leveling off or increased concentration of impurities as the rinsing of the chip progresses. A method for optimizing reuse or recycling of the water discharged from the rinse process which accurately measures the contaminants in that water.

